

Abstract of the Disclosure

A device for thermally treating at least one optical waveguide has a radiation source. A first optical system is used to direct a beam, emitted by the radiation source, onto the optical waveguide from a first side. The first optical system generates a beam profile whose extent in the transverse direction with respect to a longitudinal axis of the optical waveguide corresponds to at least twice an optical waveguide diameter. The optical waveguide is positioned completely outside a center axis of the beam profile in the transverse direction with respect to the longitudinal axis of the optical waveguide in the focusing area of the beam. A second optical system which is positioned behind the optical waveguide in the direction of a beam path of the beam, reflects and directs a beam, which is transmitted past the side of the optical waveguide, onto the optical waveguide from a second side.